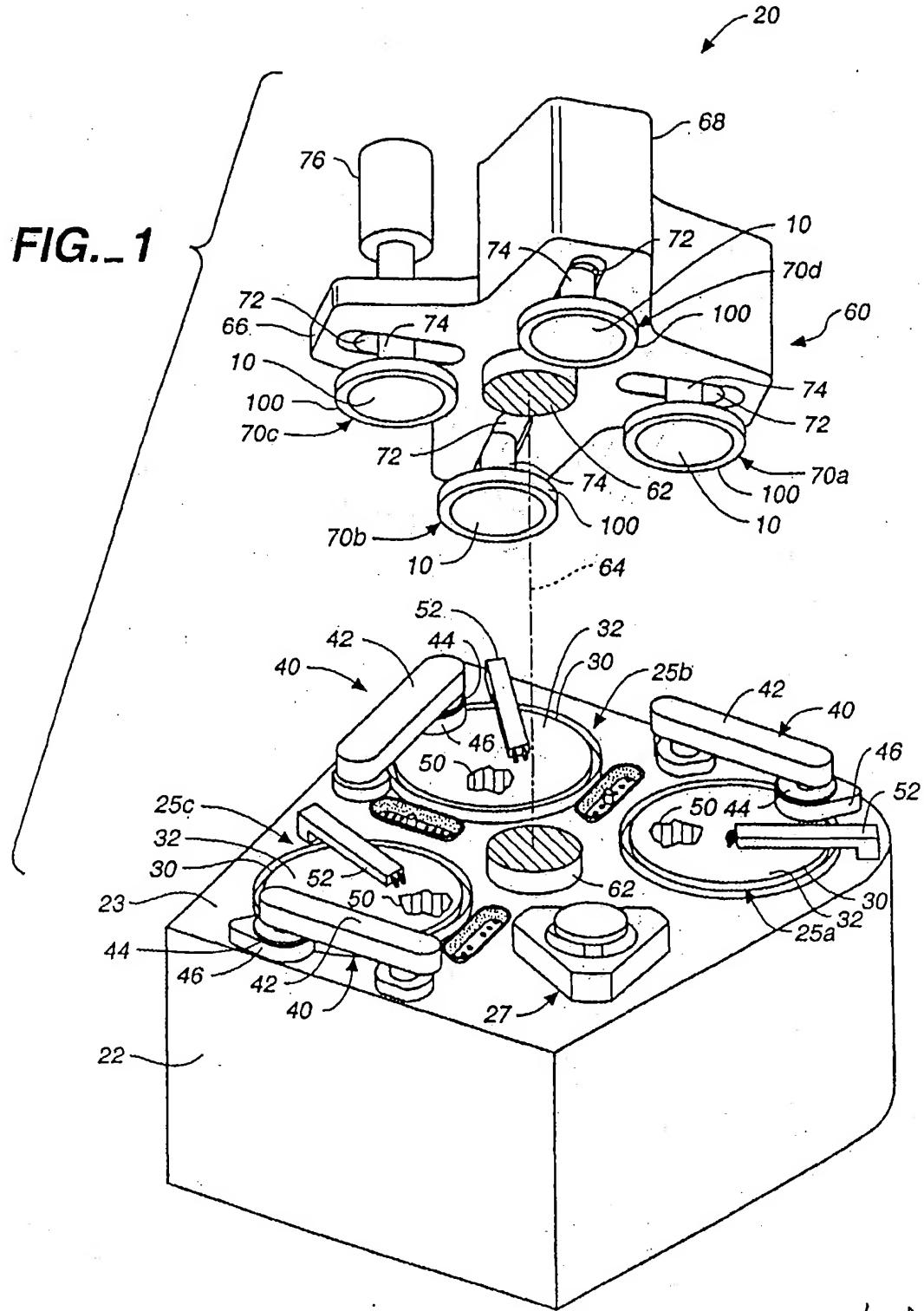


Prom Part

FIG. 1



Peter-1 / Paul-225

Prue Art

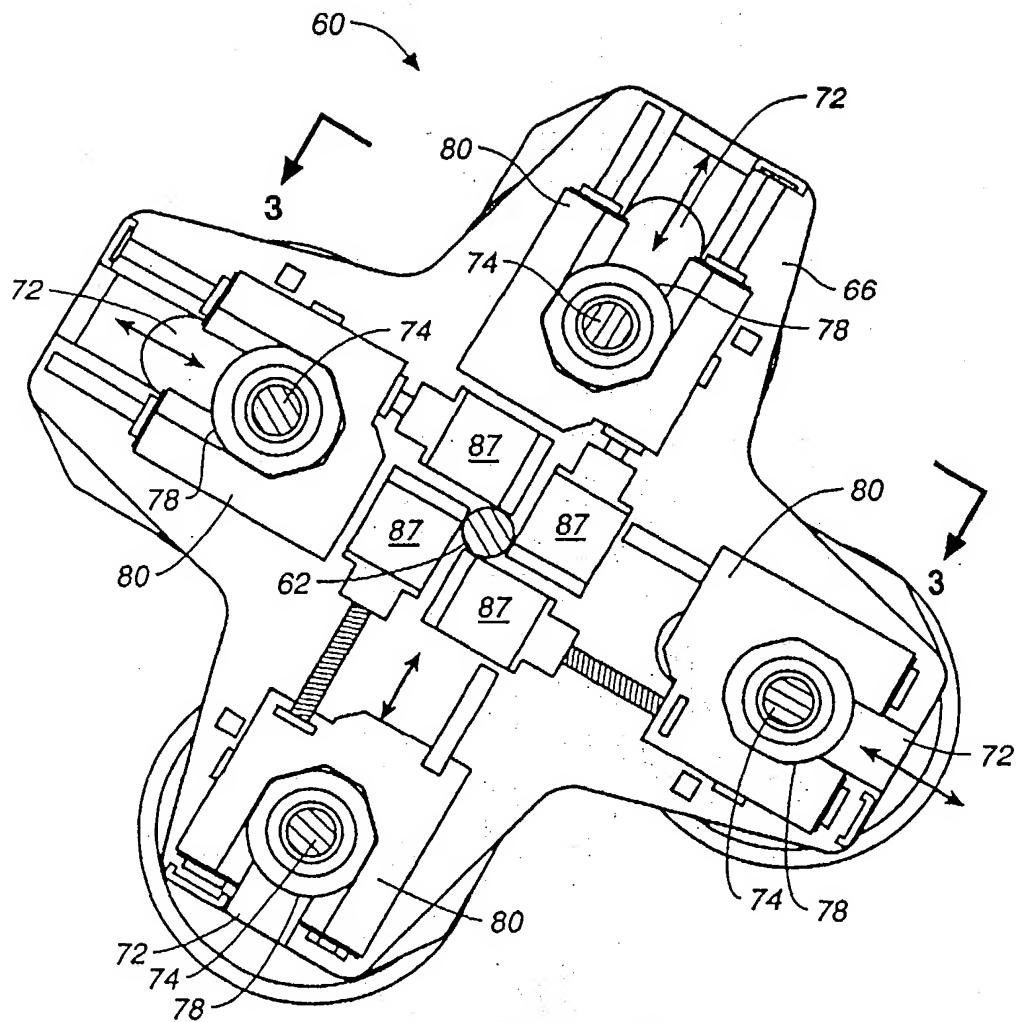
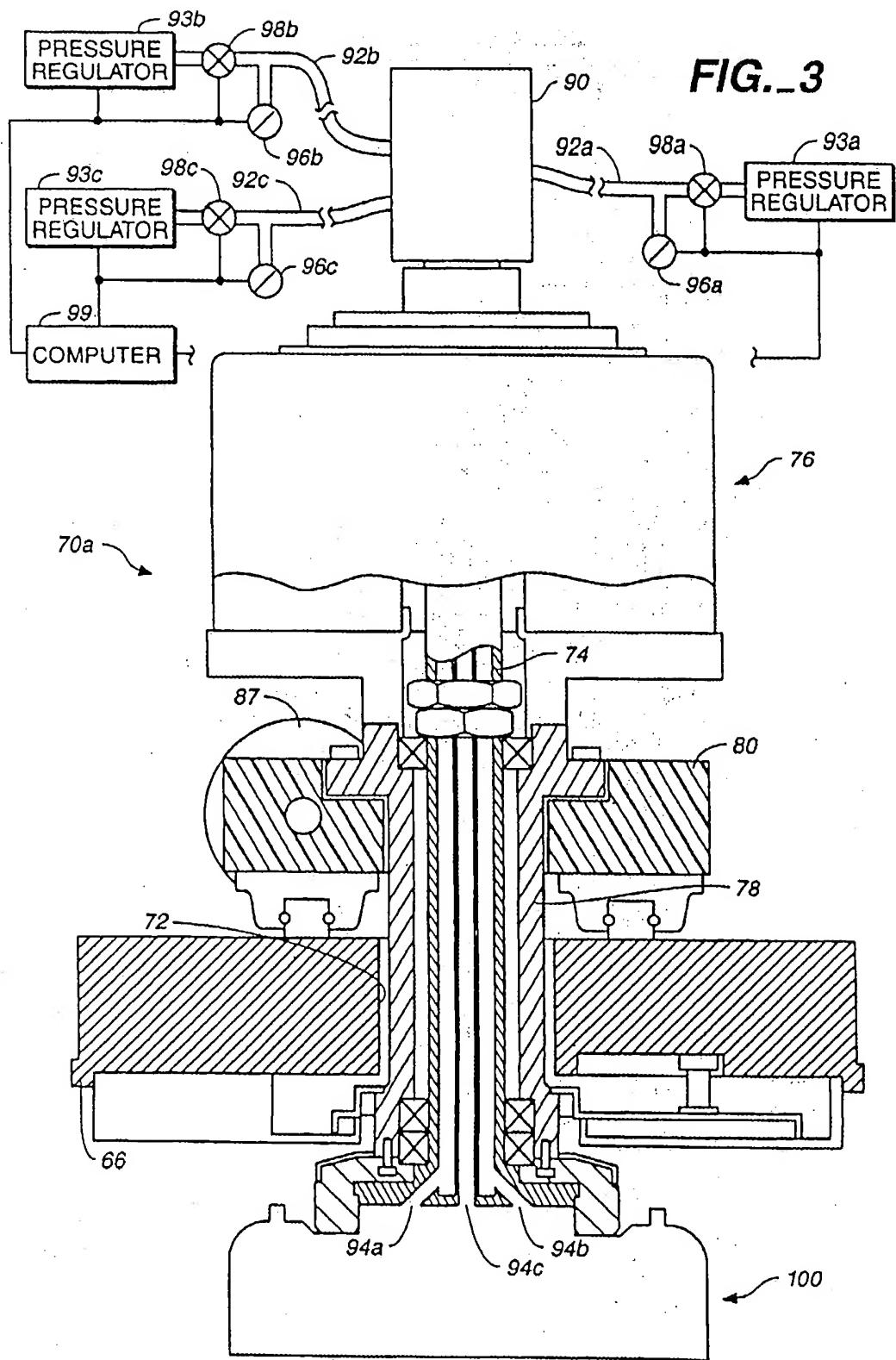


FIG.-2

Paten -1 / Part - 225

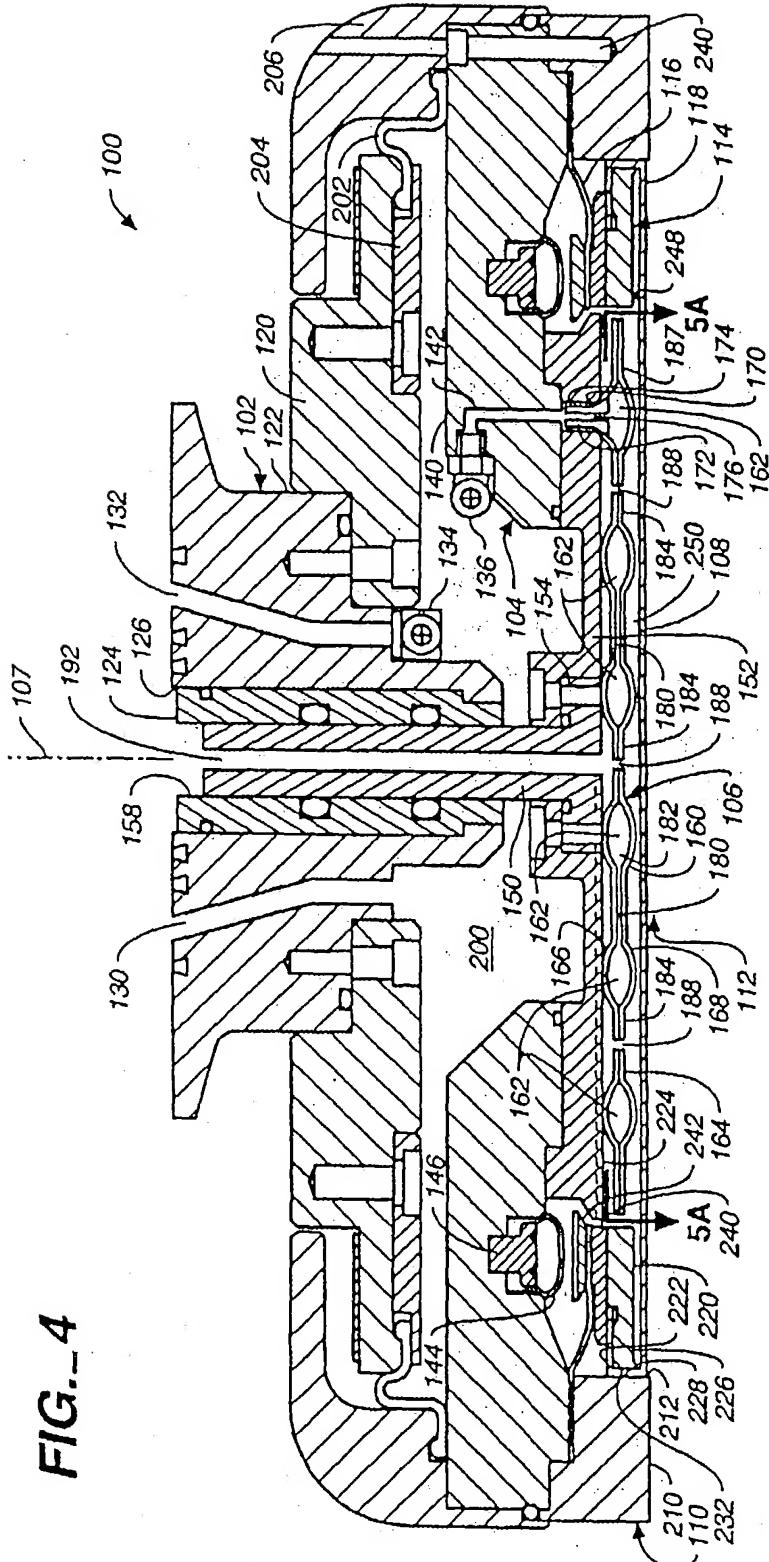
Prise Amt



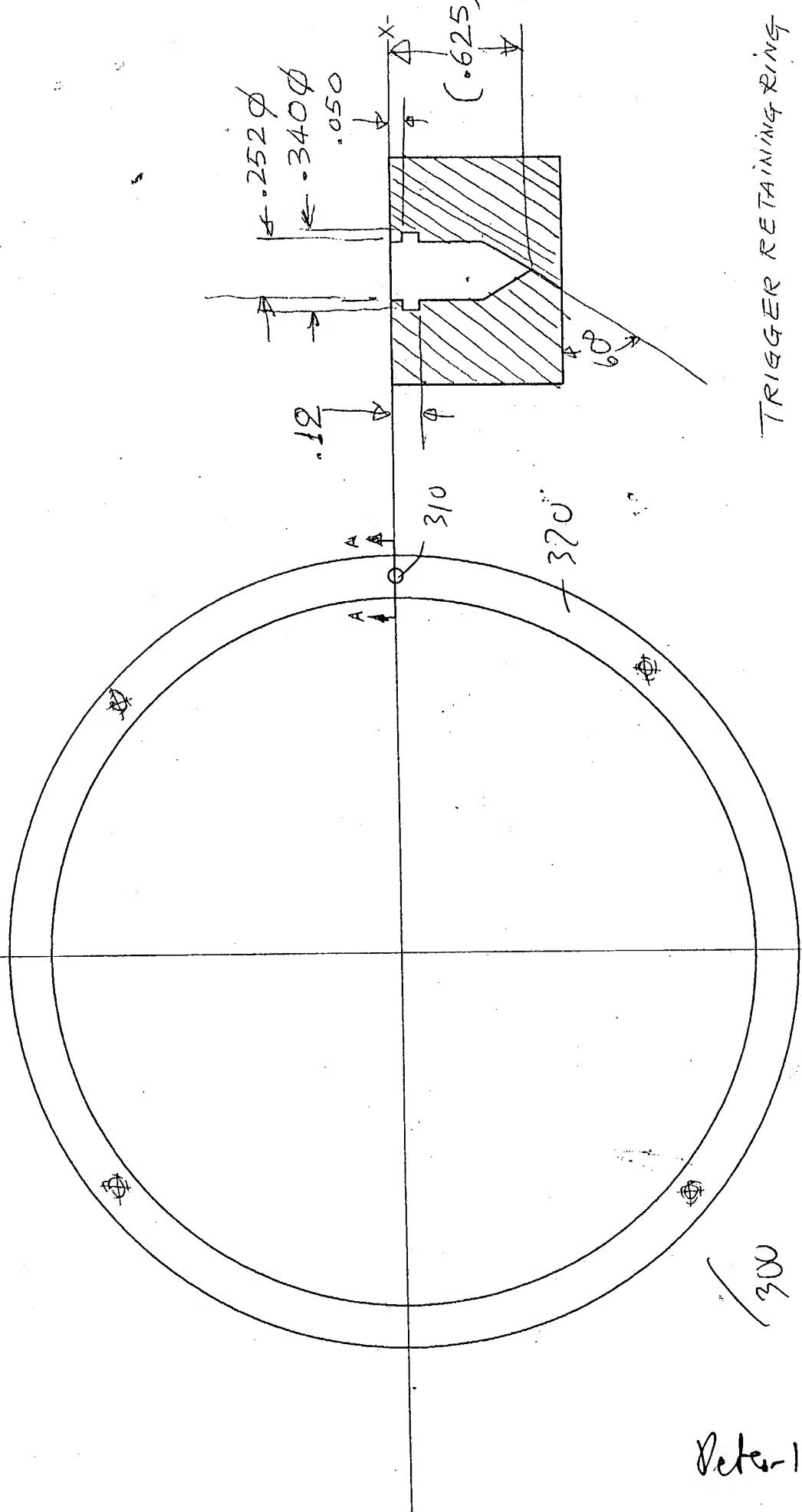
Pete-1 / Tank 225

Patent Art

FIG.-4



Paten + Pat - 225



TRIGGER RETAINING RING

6/12/03

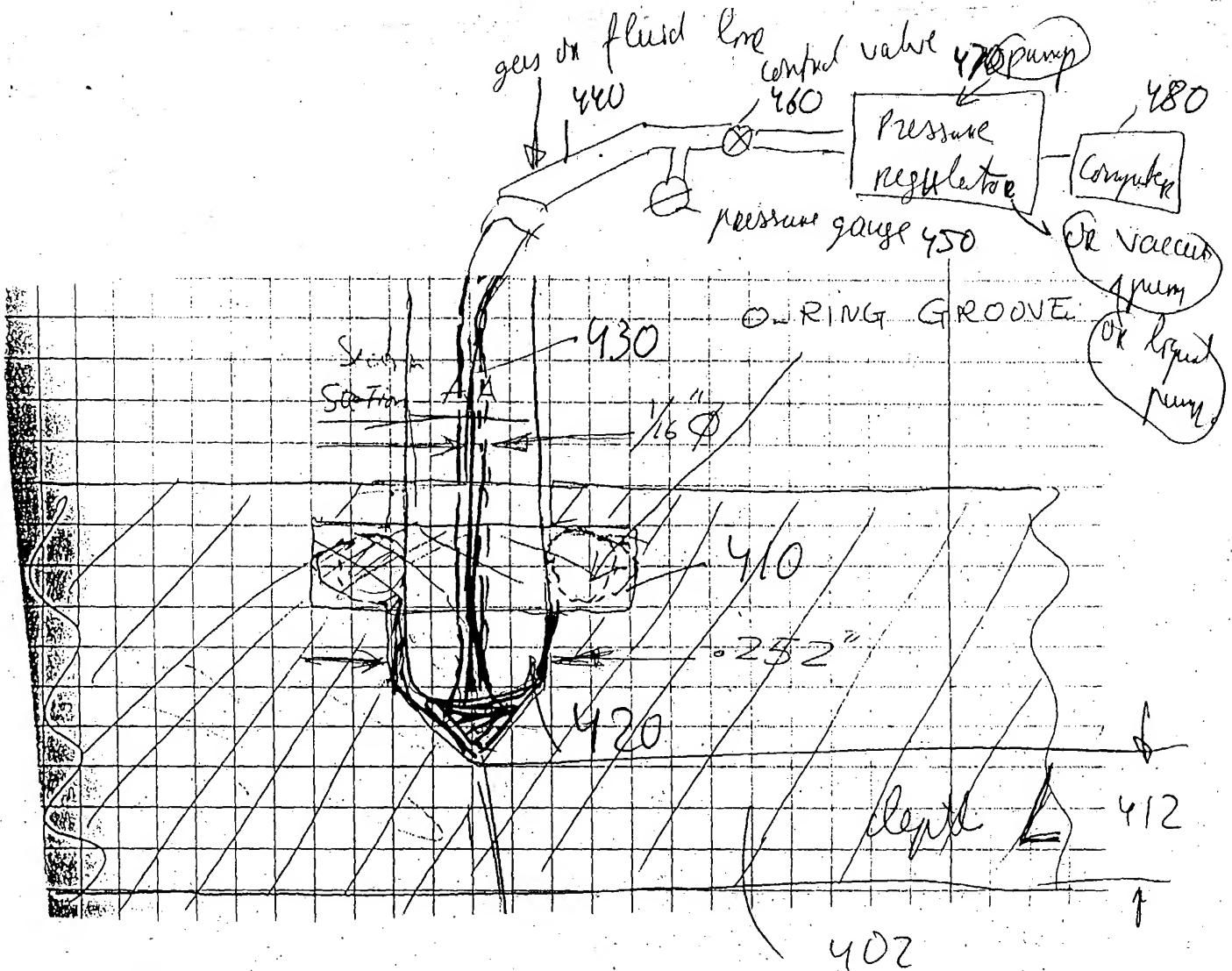
Peter Kellam

KAMET

F10.5

300

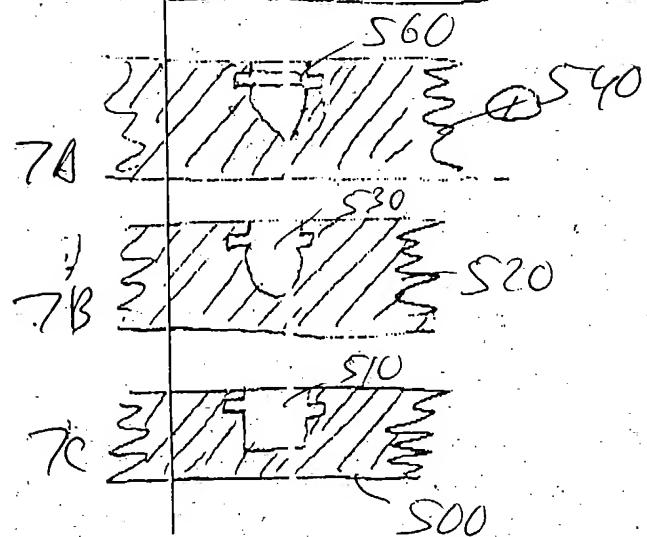
Peter-1/Tank-225



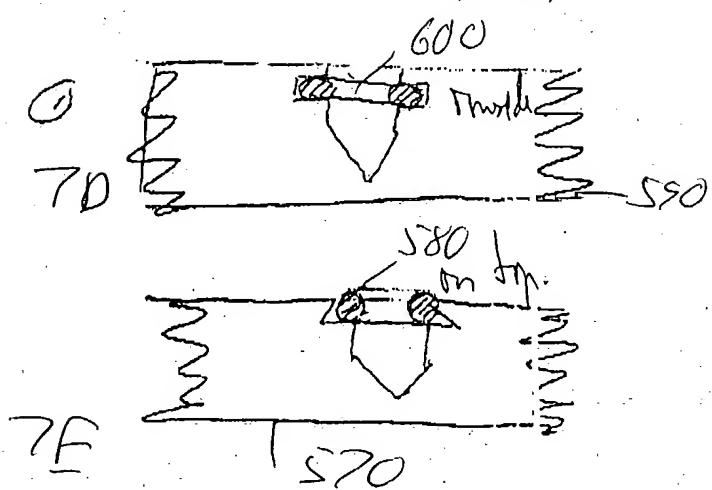
400 Fig. 6

Peter-1 Tank - 205

"SHAPE OF HOLES"



"POSITION OF O-RING"



Figs 7A-7E

Pete-1 / 5/2005

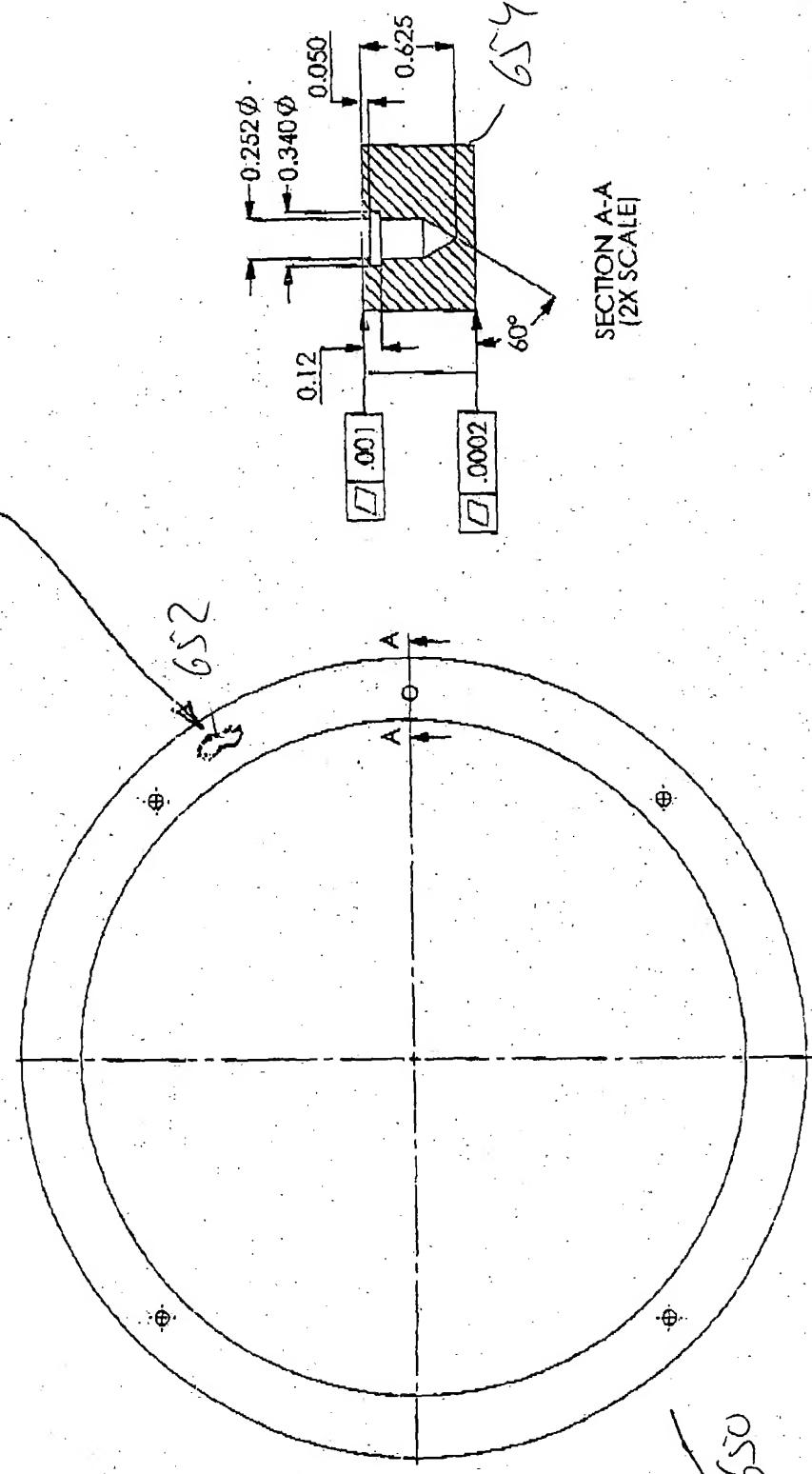
06/27/2003 11:19

408-524-7884

KAMET

PAGE - 01

Hole can be this shape



650
F67H

Peter-1/Dash 225



start

702

704

(A) filling the trigger cavity with the gas having a predetermined air pressure.

706

(B) substantially continuously measuring and maintaining the predetermined air pressure of the selected gas in the trigger cavity.

708

(C) performing a chemical mechanical polishing operation on a wafer by using the CMP apparatus having the retaining ring with the single trigger cavity under control of a computer loaded with a chemical mechanical polishing computer program.

710

NO

if the air pressure in the single trigger cavity changes beyond a predetermined threshold level?

722

yes → 720

712

(D) using the chemical mechanical polishing computer program to stop the process of performing the chemical mechanical polishing operation on the wafer.

724

↓

714

(E) replacing the retaining ring.

716

↓

(F) repeating the steps (A-E).

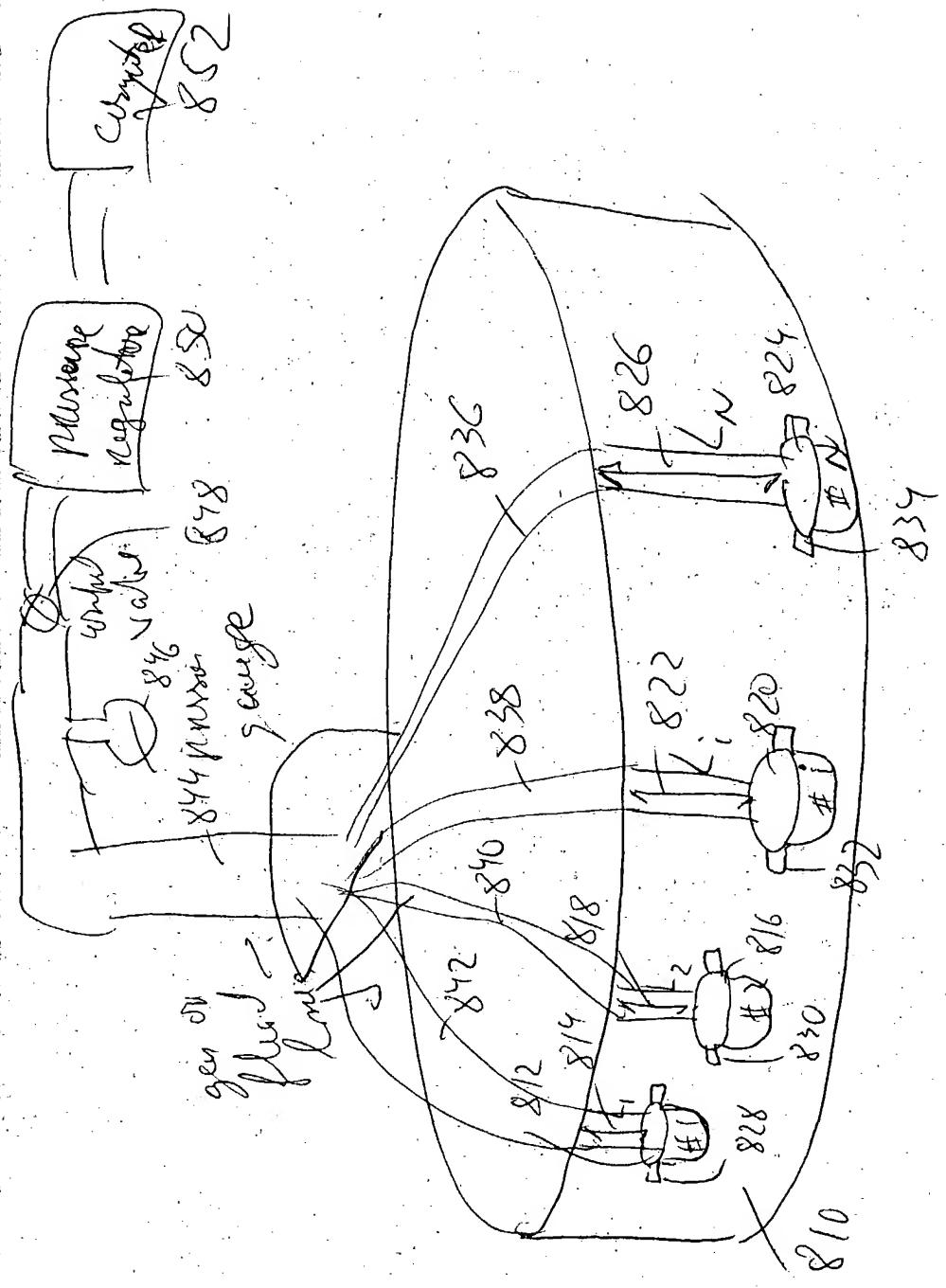
700

F.F.8

Finish

718

Pete - 1 / Park 2005



F 16.9

Pete-1/Pact-225

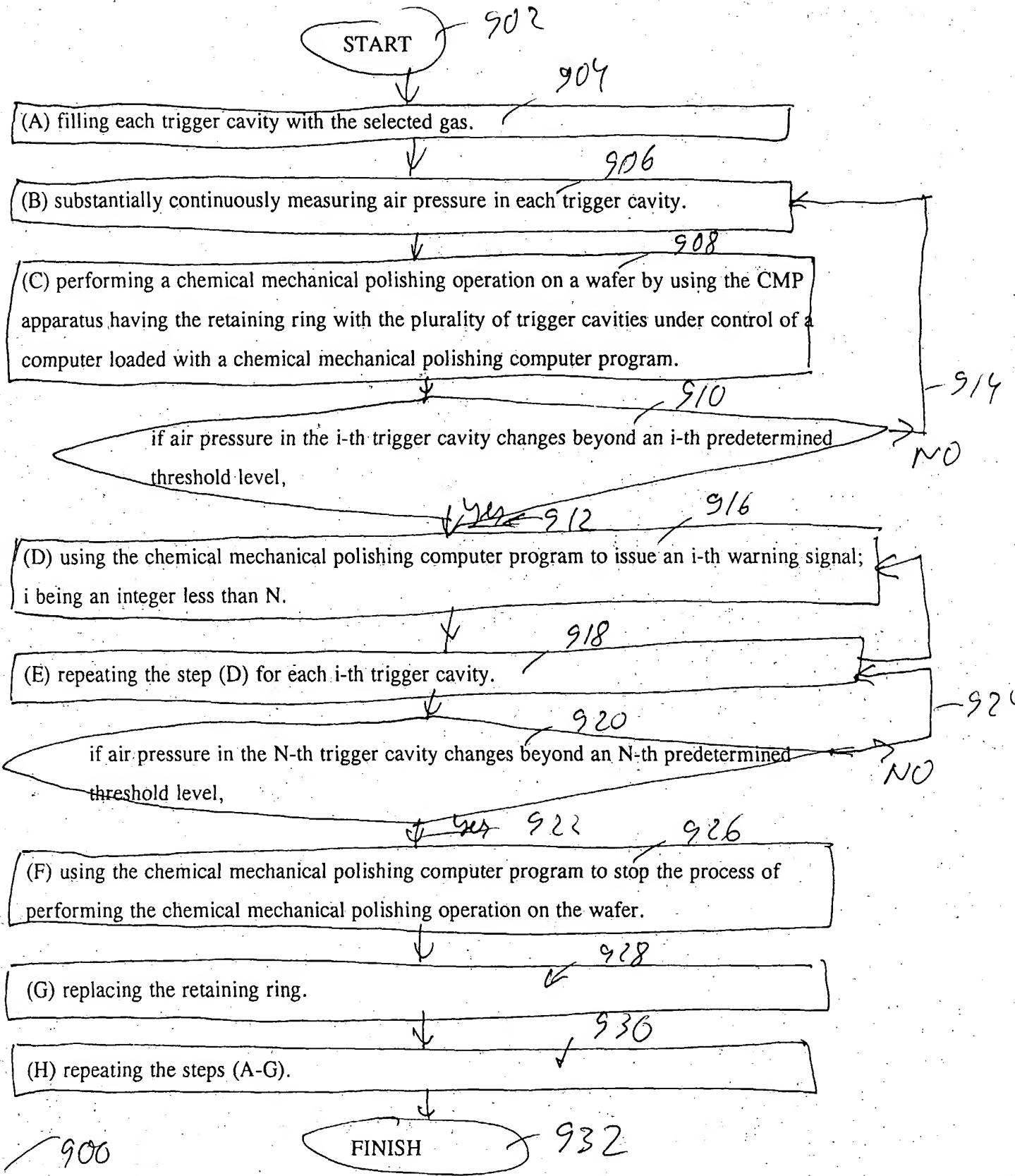


FIG. 10

Detun-1/Datt-228